

## **CLAIMS**

What is claimed is:

5        1. a measuring system of a gas-stream environment, said measuring system comprises:

      a stage, wherein said stage is located on a transport apparatus and used to place a wafer;

10      a datum platen, wherein said datum platen is located on said transport apparatus and on a side of said stage to be used to place a datum slice;

      a lens, wherein said lens is located above said stage to measure said wafer and said datum slice;

      a gas supplier, wherein said gas supplier is used to supply a gas;

15      a first gas nozzle, wherein said first gas nozzle is located on a side of said datum platen and is used to exhaust said gas;

      a second gas nozzle, wherein said second gas nozzle is located on a side of said stage and is used to exhaust said gas;

20      a first tube, wherein said first tube is connected with said first gas nozzle and said gas supplier;

      a second tube, wherein said second tube is connected with said second gas nozzle and said gas supplier;

      a transport slot, wherein said transport slot is an opening to exhaust said gas; and

25      a gas-extracting apparatus, wherein said gas-extracting apparatus connects with said transport slot by using a third tube and is used to produce a attraction to remove said gas.

2. The system according to claim 1, wherein said first tube comprises a flow rate regulating valve.

3. The system according to claim 1, wherein said second  
5 tube comprises a flow rate regulating valve.

4. The system according to claim 1, wherein said gas-extracting apparatus comprises a gas-extracting motor.

10 5. The system according to claim 1, wherein said gas-extracting apparatus comprises a venturi structure.

6. The system according to claim 1, wherein said gas is a  
inert gas.

15 7. The system according to claim 1, wherein said gas is a  
nitrogen.

8. The system according to claim 1, wherein said gas  
20 supplier comprises a flow rate regulating valve.

9. a measuring system of a gas-stream environment, said  
measuring system comprises:

a stage, wherein said stage is located on a transport apparatus  
25 and used to place a wafer;

a datum platen, wherein said datum platen is located on said  
transport apparatus and on a side of said stage to be used to place a  
datum slice;

a lens, wherein said lens is located above said stage to measure said wafer and said datum slice;

a gas supplier, wherein said gas supplier is used to supply a gas;

5 a first gas nozzle, wherein said first gas nozzle is located on a side of said datum platen to exhaust said gas and comprises a first flow rate regulating valve;

a second gas nozzle, wherein said second gas nozzle is located on a side of said stage to exhaust said gas and comprises a first flow rate regulating valve;

10 a first tube, wherein said first tube is connected with said first gas nozzle and said gas supplier;

a second tube, wherein said second tube is connected with said second gas nozzle and said gas supplier;

15 a transport slot, wherein said transport slot is an opening to exhaust said gas; and

a gas-extracting apparatus, wherein said gas-extracting apparatus connects with said transport slot by using a third tube and is used to produce a attraction to remove said gas.

20 10. The system according to claim 9, wherein said first tube comprises a flow rate regulating valve.

11. The system according to claim 9, wherein said second tube comprises a flow rate regulating valve.

25 12. The system according to claim 9, wherein said gas-extracting apparatus comprises a gas-extracting motor.

13. The system according to claim 9, wherein said gas-extracting apparatus comprises a venturi structure.

14. The system according to claim 9, wherein said gas is a  
5 inert gas.

15. The system according to claim 9, wherein said gas is a nitrogen.

10 16. The system according to claim 9, wherein said gas supplier comprises a flow rate regulating valve.

17. a measuring system of a gas-stream environment, said measuring system comprises:

15 a stage, wherein said stage is located on a transport apparatus and used to place a wafer;

a datum platen, wherein said datum platen is located on said transport apparatus and on a side of said stage to be used to place a datum slice;

20 a lens, wherein said lens is located above said stage to measure said wafer and said datum slice;

a gas supplier, wherein said gas supplier is used to supply a gas;

25 a first gas nozzle, wherein said first gas nozzle is located on a side of said datum platen and on said transport apparatus to exhaust said gas;

a second gas nozzle, wherein said second gas nozzle is located on a side of said stage and on said transport apparatus to exhaust said gas;

a first tube, wherein said first tube comprises a first flow rate regulating valve and is connected with said first gas nozzle and said gas supplier;

5       a second tube, wherein said second tube comprises a second flow rate regulating valve and is connected with said second gas nozzle and said gas supplier;

      a transport slot, wherein said transport slot is an opening to exhaust said gas; and

10      a gas-extracting apparatus, wherein said gas-extracting apparatus connects with said transport slot by using a third tube and is used to produce a attraction to remove said gas.

15      18.     The system according to claim 17, wherein said gas-extracting apparatus comprises a venturi structure.

19.     The system according to claim 17, wherein said gas is a inert gas.

20      20.     The system according to claim 17, wherein said gas is a nitrogen.